

ABSTRACT:

LITHOGRAPHIC PROJECTION APPARATUS, DEVICE MANUFACTURING
METHOD AND DEVICE MANUFACTURED THEREBY

A lithographic projection apparatus comprising a radiation system for supplying a projection beam of radiation, a mask table for holding a mask, a substrate table for holding a substrate and a projection system for imaging an irradiated portion of the mask onto a target portion of the substrate. Either or both of the radiation system and the projection system is supplied with an inert gas at a pressure of from 0.1 to 10 Pa in order to suppress contamination, for example by hydrocarbon molecules, of any optical components in the system(s).

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